Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L18	16	((alignment adj mark) near (form or forming or formed or formation)) near5 (sequentially or serially or series or time).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:26
L19	21	((alignment adj mark) near (form or forming or formed or formation)) near10 (sequentially or serially or series or time).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:07
L20	24	((alignment adj mark) near (form or forming or formed or formation)) near10 (sequentially or serially or series or time or sequence or sequential).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:08
L21	267	((alignment adj mark) near (form or forming or formed or formation)) near10 (sequentially or serially or series or time or sequence or sequential)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:08
L22	12	((alignment adj mark) near (form or forming or formed or formation)) near10 (sequentially or serially or series or time or sequence or sequential) and membrane	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:10
L23	3	((alignment adj mark) near (form or forming or formed or formation)) near10 (sequentially or serially or series or time or sequence or sequential) and membrane and (electron near (scatter or scattering or scatterer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:10
L24	36	(alignment adj mark) and membrane and (electron near (scatter or scattering or scatterer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:11
L25	2	(alignment adj mark) and membrane and (electron near (scatterer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:11
L26	7	mask and (electron near (scatterer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:12

L27	1191	(mask and (electron near (scatterer or scattering or scatter)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:12
L28	20	(mask and (electron near (scatterer or scattering or scatter))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:12
L29	14	(mask with (electron near (scatterer or scattering or scatter))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:13
L30	0	((alighnment adj mark) with (electron near (scatterer or scattering or scatter))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:13
L31	2	((alignment adj mark) with (electron near (scatterer or scattering or scatter))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:13
L32	7	((alignment adj mark) with (electron near (scatterer or scattering or scatter)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:14
L33	10	((alignment adj mark) with (mask adj board))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:15
L34	600	((alignment adj mark) with (board))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:15
L35	509	((alignment adj mark) near10 (board))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:15
L36	208	((alignment adj mark) near10 (form or forming or formed or formation) near10 (board))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:15

L37	10	((alignment adj mark) near10 (form or forming or formed or formation) near10 (board)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:15
L38	5	((alignment adj mark) near10 (form or forming or formed or formation) near10 (board)).clm. and mask.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:16
L39	4	((alignment adj mark) near10 (form or forming or formed or formation) near10 (board)).clm. same mask.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:16
L40	39	(alignment adj mark) near10 (form or forming or formed or formation) near10 (board) same mask	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:17
L41	2	(alignment adj mark) near10 (form or forming or formed or formation) near10 (board) same mask and stencil	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:17
L42	2	(alignment adj mark) near10 (board) same mask and stencil	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:17
L43	2	(alignment adj mark) near10 (board) same mask and membrane	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:17